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ABSTRACT OF THE DISCLOSURE

A projection exposure apparatus includes an illumination optical system for illuminating a reticle having a pattern, with illumination light supplied from a light source, a projection optical system for projecting the pattern onto a substrate by use of the illumination light, a measuring system for measuring angular distribution of the illumination light, and an adjusting system for changing angular distribution of the illumination light, entering the projection optical system, on the basis of measurement by the measuring system and in accordance with a distance from an optical axis.

SECRET